

Get Equivalent GC-MS Results Faster with Restek's GC Accelerator Kit and EZGC Method Translator

Would you like to significantly reduce your current GC-MS analysis time while maintaining the same chromatographic separation? The combination of using a GC Accelerator oven insert kit and adapting an existing method to a scaled-down, more efficient column using our EZGC method translator is a surprisingly simple means of speeding up your analyses to get similar results faster.

The GC Accelerator kit for Agilent GCs helps increase speed because the insulated inserts fill the oven cavity, creating a smaller volume to heat and cool (Figure 1). This allows you to significantly increase ramp rates on your existing instrument, which provides an easy means of speeding up analysis time without any changes to hardware or software. Also, GC Accelerator inserts were designed with GC-MS users in mind, so they fit easily into the oven without interfering with an inlet installed in the front position or with the MS transfer line interface.

Faster analyses can also be obtained on any GC by moving to a shorter column with a narrower inner diameter (ID) and thinner film. A smaller ID and thinner film results in a more efficient column that produces narrower peaks, which allow relative peak separations to be maintained and compressed into shorter run times. Note that when changing column dimensions, it's important to adjust the inner diameter and film thickness proportionally so the phase ratio stays the same. The more efficient column will also be shorter than the original. The more efficient column will have more plates per meter, but to properly scale down you need to maintain the same number of total plates, which is why the new column will be shorter. However, just properly scaling down the column won't give you the same results in less time. To get the same results faster, you need to adjust key method parameters to account for the shorter, more efficient column. Fortunately, that's easy to do using EZGC method translation software. Let's walk through an example to show you how.

reducing oven volume, which allows for faster ramp rates.

Figure 1: GC Accelerator oven inserts speed up analysis times by



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For our demonstration, let's say you're performing PCB analyses on an Agilent GC-MS using the conditions shown in Figure 2. You're happy with the separation, but want to shorten analysis time so you can analyze more samples per shift. The first step is to select a scaled-down column with the same phase ratio and total number of theoretical plates.





In this example, we are switching from a 30 m, 0.25 mm, 0.25 μ m column to a 20 m, 0.15 mm, 0.15 μ m column. To obtain the translated method conditions that provide the same chromatographic separation in less time on the new column, follow the steps below. Go to **www.restek.com/ezgc-mtfc** if you'd like to try using the *EZGC* method translator (Figure 3) yourself as we move through the example.

EZGC®N	/let	hoc	l Tr	ans	lato	or				
Carrier Ga	s		Ori	igina	il 👘	Tra	insl	atio	n	
			He	lium	~	н	elium		~	
Column										
Length					30.00			15	.00	m
Inner Diameter					0.25			0	.25	mm
Film Thickness					0.25			0	.25	μm
Phase Ratio					250			2	250	
Control Pa	rame	eters								
Column Flow			-	1	1.40			1	.40	mL/min
Average Velocit	y				42.74			60	.44	cm/sec
Holdup Time					1.17			0	.41	min
Inlet Pressure	psi	\sim			11.42			3	.77	psi
Outlet Pressure	e (abs)				0.00			0	.00	psi
				Atm	Vacuum		Atm	Vacu	um	400
Oven Prog	ram									
 Isothermal Ramps 		(Ramp Rate C/min)	Temp (°C)	Hold Time (min)	Ra R (°C)	imp ate /min)	Temp (°C)	Hol Tim (min	id ie n)
Number of Ram	ps (1-4)			40	1			40	0.3	35
1			8.5	330	1		24	330	0.3	35
Control M	etho									
		Con	stant F	low		\sim				
Results	5	olve f	or 🔍 E	fficien	icy 🔍 S	peed (🛛 Tra	nslate	•	Custom
Run Time					36.12			12	.78	min
Speed								2	83	×

Step 2: Enter your current column dimensions.

				/
Carrier Gas	Original		Translation	
	Helium	\mathbf{v}	Helium 🗸	8
Column				
Length	3	0.00	15.0	0 m
Inner Diameter		0.25	0.2	5 mm
Film Thickness		0.25	0.2	5 µm
Phase Ratio		250	25	0

Step 3: Enter your current method's column flow. Note that average velocity, holdup time, and inlet pressure will autofill based on the column flow you specify. Because this is a MS method, make sure the outlet pressure (abs) value is set to 0 psi and the vacuum button is selected. These are the default selections, but note that the modeler output would be different if you were using an FID, for instance, and the outlet pressure (abs) was atmospheric pressure instead of the vacuum generated by a mass spectrometer.

EZGC [°] Met	nod Translato	br
Carrier Gas	Original	Translation
	Helium 🗸	Helium 🗸
Column		
Length	30.00	15.00 m
Inner Diameter	0.25	0.25 mm
Film Thickness	0.25	0.25 µm
Phase Ratio	250	250
Control Parame	ters	
Column Flow	→ 1.00	→ 1.00 mL/mi
Average Velocity	36.12	51.08 cm/sec
Holdup Time	1.38	0.49 min
Inlet Pressure psi	✓ 7.38	0.91 psi
Outlet Pressure (abs)	0.00	0.00 psi
	Atm Vacuum	Atm Vacuum

tep 4: Enter	your	curr	em		enpro	gram	•		
EZGC [°] M	/leth	bd	Tra	ans	lato	r			
Carrier Ga	S		Ori	gina	I	Trans	atio	n	
			He	lium	\sim	Helium	n	~	
Column									
Length					30.00		15	.00	m
Inner Diameter					0.25		0	.25	mm
Film Thickness					0.25		0	.25	μm
Phase Ratio					250		2	50	
Control Pa	ramete	ers							
Column Flow			⇒		1.00	⇒	1	.00	mL/mi
Average Velocit	ty				36.12		51	.08	cm/se
Holdup Time			_		1.38		0	.49	min
Inlet Pressure	psi	4			7.38		0	.91	psi
Outlet Pressure	e (abs)			-	0.00		0	.00	psi
4			_	Atm	Vacuum	Atr	Vacu	um	
Oven Prog	ram								
 Isothermal Ramps 		Ra Ri (°C/	mp ate 'min)	Temp (°C)	Hold Time (min)	Ramp Rate (°C/min)	Temp (°C)	Ho Tim (mi	ld ne n)
Number of Ram	ps (1-4)			40	2		40	C	.7
2			30	240	2	85	240	C).7
			10	340	5	28.3	340	1.	75

Step 5: Make sure the control method is correct and the default radio button "Translate" is selected. By choosing the "Translate" option, you are asking the *EZ*GC method translator to balance speed and efficiency.

Ramps		Ramp Rate (°C/min)	Temp (°C)	Hold Time (min)	Ramp Rate (°C/min)	Temp (°C)	Hold Time (min)
Number of Ramps	(1-4)		40	2		40	0.7
2		30	240	2	85	240	0.7
		10	340	5	28.3	340	1.75
Results	Solve	for 🔍 E	fficien	cy 🔍 Sp	peed O Tra	inslate	e 🔍 Cu
Results Run Time	Solve	for 🔍 E	fficien	cy • Sr 25.67	peed O Tra	anslate 9	• • Cu:
Results Run Time Speed	Solve	for 🔍 E	fficien	cy 🔍 Sp 25.67	oeed O Tra	enslate 9 2	• • Cu: .04 mi .84 x

Step 6: Enter the new column dimensions and the *EZ*GC method translator will do the rest of the work and provide the following properly translated method parameters that will give an equivalent separation in less time on the scaled-down column you selected.

- a) New column flow and the subsequently calculated flow-related parameters.
- b) New oven ramp rates.
- c) New shorter analysis time for the same separation.

Carrier Gas Original Translation Helium Helium Helium Length 30.00 20.00 m Inner Diameter 0.25 0.15 mm Film Thickness 0.25 0.15 µm Phase Ratio 250 250 Column Flow 1.0 a) 0.60 mL Average Velocity 36.12 34.27 cm/ Holdup Time 1.38 0.97 min Inlet Pressure (abs) 0.00 0.00 psi Atm Vacuum Atm Oven Program Atm Vacuum	'min 'sec
Helium Helium Helium Column 30.00 20.00 m Length 30.00 20.00 m Inner Diameter 0.25 0.15 mm Film Thickness 0.25 0.15 µm Phase Ratio 250 250 250 Control Parameters 0.60 mL Column Flow 1.0 → 0.60 mL Average Velocity 36.12 34.27 cm/ Holdup Time 1.38 0.97 min Inlet Pressure psi ∨ 7.38 24.08 psi Outlet Pressure (abs) 0.00 0.00 psi Oven Program Atm Vacuum Atm Vacuum Atm Vacuum	'min 'sec
Column Length 30.00 20.00 m Inner Diameter 0.25 0.15 mm Film Thickness 0.25 0.15 µm Phase Ratio 250 250 Control Parameters 250 250 Column Flow 1.0 a) → 0.60 mL/ 0.60 mL/ Average Velocity 36.12 34.27 cm/ Holdup Time 1.38 0.97 min Inlet Pressure (abs) 0.00 0.00 psi Atm Vacuum Atm Vacuum	min sec
Length 30.00 20.00 m Inner Diameter 0.25 0.15 mm Film Thickness 0.25 0.15 µm Phase Ratio 250 250 Control Parameters 200 m 0.60 mL Average Velocity 36.12 34.27 cm/ Holdup Time 1.38 0.97 min Inlet Pressure (abs) 0.00 0.00 psi Atm Vacuum Atm Vacuum	'min 'sec
Inner Diameter 0.25 0.15 mm Film Thickness 0.25 0.15 µm Phase Ratio 250 250 250 Control Parameters Column Flow 1.0 a) → 0.60 mL Average Velocity 36.12 34.27 cm/ Holdup Time 1.38 0.97 min Inlet Pressure psi ∨ 7.38 24.08 psi Outlet Pressure (abs) 0.00 0.00 psi	min sec
Film Thickness 0.25 0.15 µm Phase Ratio 250 250 Control Parameters 0.60 mL Average Velocity 36.12 34.27 cm/ Holdup Time 1.38 0.97 min Inlet Pressure (abs) 0.00 0.00 psi Atm Vacuum Atm Vacuum Atm Vacuum	'min 'sec
Phase Ratio 250 250 Control Parameters Column Flow → 1.0 → 0.60 mL/ Average Velocity 36.12 34.27 cm/ Holdup Time 1.38 0.97 min Inlet Pressure psi ∨ 7.38 24.08 psi Outlet Pressure (abs) 0.00 0.00 psi Atm Vacuum Atm Vacuum	'min 'sec
Control Parameters Column Flow Average Velocity Average Velocity Holdup Time 1.38 0.97 Inlet Pressure psi Outlet Pressure (abs) 0.00 0.00 Atm Vacuum Atm Verage	/min /sec
Column Flow Average Velocity Holdup Time 1.38 0.97 min Inlet Pressure psi ↓ Outlet Pressure (abs) 0.00 0.00 Atm Vacuum Atm Vacuum	/min sec
Average Velocity Holdup Time 1.38 0.97 min Inlet Pressure psi V 0.00 0.0	sec
Holdup Time 1.38 0.97 min Inlet Pressure psi V 7.38 24.08 psi Outlet Pressure (abs) 0.00 0.00 psi Atm Vacuum Atm Vacuum Oven Program	
Inlet Pressure psi v 7.38 24.08 psi Outlet Pressure (abs) 0.00 0.00 psi Atm Vacuum Atm Vacuum	
Outlet Pressure (abs) 0,00 0,00 psi Atm Vacuum Atm Vacuum	
Atm Vacuum Atm Vacuum Oven Program	
Oven Program	
Olastharmal	
Ramp Hold Ramp Hold Ramp Rate Temp Time Ramps ("C/min) ("C) (min) ("C/min)	b
Number of Ramps (1-4) 40 2 40 1.4	
2 30 240 2 42.7 240 1.4	
10 340 5 14.2 340 3.5	
Control Method	
Constant Flow	
Results Solve for • Efficiency • Speed • Translate • Cus	tom
Run Time 25.67 (C) 18.03 min	
Speed 1.42 x	
Use Flow Calculator Values	

In this example, we're seeing a savings of almost 8 minutes, almost 30%, in analysis time. Put simply, this change would allow an instrument to complete a sequence of samples that normally would take 8 hours in a little more than 5.5 hours. We also see an example of the value of using the GC Accelerator oven insert. Figure 4 displays the new oven program, which has a starting ramp of 42.7 $^{\circ}$ C/ min up to 240 $^{\circ}$ C. A standard 100/120 V oven just won't ramp that fast. In fact, even the faster-ramping 200/220/230/240 V oven only barely meets this requirement, and then only if everything is in pristine condition. Retention times can vary significantly if the oven isn't able to achieve the programed ramp rate, causing problems with peak identification and quantitation. However, aggressive ramp rates like this one can reliably be achieved with the GC Accelerator inserts installed. Table I compares the maximum rates that can be obtained with and without the inserts installed in Agilent ovens.

Figure 4: The GC Accelerator insert kit reduces oven volume, which shortens heating/cooling times and allows aggressive ramp rates to be met.

Oven Program							
 Isothermal Ramps 	Ramp Rate (°C/min)	Temp (°C)	H Ti (mi)	Ramp Rate (°C/min)	Temp (°C)	Hold Time (min)	b
Number of Ramps (1-4)		40	2	1	40	1.4	
2	30	240	2	42.7	240	1.4	
	10	340	5	14.2	340	3.5	

Table I: Maximum Ramp Rates in an Agilent GC-MS Oven with and without GC Accelerator Inserts Installed.

T (°C)	120 V Oven Ram	p Rate (°C/min)	>200 V Oven Ramp Rate (
Temperature Range (°C)	Without GC Accelerator	With GC Accelerator	Without GC Accelerator	With GC Accelerator			
50–70	75	120	120	120			
70-115	45	95	95	120			
115-175	40	65	65	110			
175-300	30	40	45	70			
300-350*	20	30	35	65			

* Agilent ovens are programmable to 450 °C, but this product was only tested to 350 °C. Prior to analysis, confirm the analytical column can withstand the temperatures and ramp rates you plan to use.



With the GC Accelerator kit installed, you can obtain the same separation while speeding up your analysis. To show you the results, we entered the translated method parameters into the Pro *EZ*GC chromatogram modeler (available at **www.restek.com/proezgc**). As demonstrated by the simulated chromatogram in Figure 5, comparable chromatography can be achieved in a much faster analysis time using the new column dimensions and instrument conditions. In fact, with the final peak eluting at 11.5 minutes under the new set of conditions, thought could be given to changing the end of the method to ramp quicker or end sooner, resulting in an even shorter analysis than the direct translation calculates.

The last thing you'll need to keep in mind if you implement these changes is that the move to a narrower, thinner film column will best be paired with the adoption of a split injection mode. It's possible that you're currently using a splitless injection to enhance the sensitivity of your analysis, but the much higher efficiency this change will provide produces narrower, taller peaks, which itself is a boost in sensitivity. That boost should allow you to still meet your detection limits even when using a split injection.

The value of the split injection is two-fold. First, if there were any loading capacity concerns with a thinner film producing overloaded, fronting peaks, the split injection will take care of that. Second, the biggest benefit is the very rapid transfer of the sample onto the column, which will help keep the bands of molecules narrow, and, as a result, your peaks narrow. The relatively slow transfer time of a splitless injection, especially one into a relatively wide inlet liner (e.g., a 4 mm ID single taper with wool), will cause band broadening, and consequently, peak widening, and that might negate some of the efficiency benefits of the new column dimension. Moving to a split injection will also mean you can keep using your typical liner instead of trying to switch to a narrower one to maintain overall efficiency.

In conclusion, equivalent chromatographic results can be obtained in much faster analysis times for many applications by moving to a scaled-down, more efficient column with the same phase ratio. *EZGC* method translation software from Restek makes it exceptionally easy to do this on any GC system, and the translated method can be even further optimized if desired. When moving to a translated method, make sure that the new oven program does not exceed the capabilities of your oven. Agilent GC-MS users can use GC Accelerator oven inserts to achieve more aggressive oven programs. These inserts reduce oven volume, which allows the oven to heat and cool faster, ultimately resulting in faster analyses.







GC Accelerator Oven Insert Kit for Agilent 6890 and 7890 instruments

- Get the same GC separation in less time—use a GC Accelerator kit and the *EZ*GC method translator to accurately convert methods to a scaled-down column format.
- Scaled-down methods let you speed up analysis time and increase sample throughput without capital investment.
- GC Accelerator kit installs easily without damaging the GC column or interfering with the MS interface.

Designed with GC-MS users in mind, the GC Accelerator kit provides a simple way to speed up sample analysis. By reducing oven volume, these inserts allow faster ramp rates to be attained, which reduces oven cycle time and allows for increased sample throughput and more capacity to process rush samples. When faster ramp rates are used, existing methods can be accurately scaled down to smaller, high-efficiency, narrow-bore columns using Restek's *EZ*GC method translator. With a scaled-down column, a properly translated method, and a GC Accelerator kit, you can obtain the same chromatographic separation—often with greater sensitivity—in a fraction of the time without making a capital investment.

Description

GC Accelerator Oven Insert Kit for Agilent 6890 and 7890 instruments kit 23849
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Speed Up and Simplify GC Method Development with **Restek's EZGC Online Suite**

- Model chromatograms
- Get column recommendations
- Translate methods
- Calculate flows

Get started at www.restek.com/ezgc



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